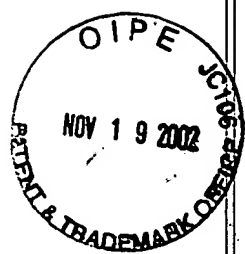


1763



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Appln. Of: YUDA et al.

Serial No.: 09/820,149

Filed: March 28, 2001

For: REMOTE PLASMA APPARATUS FOR PROCESSING ...

#16A  
4/22/02  
MLJ

Group: 1763

Examiner: ANNA M. CROWELL

DOCKET: NEC WNZ-2310

Assistant Commissioner of Patents & Trademarks  
Washington, D.C. 20231

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AMENDMENT A

Dear Sir:

This Amendment is being filed in response to the Official Action mailed  
August 14, 2002.

Please amend the Application as follows:

IN THE SPECIFICATION:

Please replace the paragraph bridging pages 1 and 2, beginning at page 1, line 17, with  
the following rewritten paragraph:

--In an exemplary remote plasma CVD process, two types of gases are used. One type of  
[gases] gas is a plasma material gas that is decomposed, and/or energized, and changed into  
plasma including radicals and excited species, while another type of gas is a deposition material  
gas that reacts with the radicals and excited species in a gas phase reaction. For example, the  
former is oxygen (O<sub>2</sub>) gas while the latter is monosilane or silane (SiH<sub>4</sub>) gas. In a remote plasma  
CVD process, oxygen gas is at first energized and changed into plasma within a plasma  
generation region. The plasma includes excited species and radicals which are excited oxygen

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